

Resource Summary Report

Generated by RRID on Aug 5, 2026

Oxford: Ionfab Ion Beam Plasma Technology

RRID:SCR_020358

Type: Tool

Proper Citation

Oxford: Ionfab Ion Beam Plasma Technology (RRID:SCR_020358)

Resource Information

URL: <https://plasma.oxinst.com/products/ion-beam/ionfab>

Proper Citation: Oxford: Ionfab Ion Beam Plasma Technology (RRID:SCR_020358)

Description: Ion beam etch and deposition system is used for high quality material processing. Systems have flexible hardware options including open load, single substrate load lock, and cassette to cassette.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: Ionfab Ion Beam Plasma Technology

Resource ID: SCR_020358

Alternate IDs: Model_Number_Ionfab

Record Creation Time: 20220129T080349+0000

Record Last Update: 20260801T190656+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: Ionfab Ion Beam Plasma Technology.

No alerts have been found for Oxford: Ionfab Ion Beam Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.